



ECLIPSE LV-N



Industrial Microscopes
LV150N / LV150NL / LV150NA
LV100ND / LV100DA-U



Together with new optics, ECLIPSE is evolving to the next stage.

The ECLIPSE microscope body has been modularized to meet industrial microscope applications in diverse fields of industry, including semiconductor devices, packaging, FPDs, electronic components, materials, and precision molds.

The ECLIPSE LV Series, with stand units and illumination units selectable according to observation method and purpose to meet a variety of observation methods, has gained a new optical system and new features in its continued evolution.

Four types – motorized and manual types plus dedicated reflected illumination and combined reflected/transmitted illumination types – are available to meet any application.

CFI60-2

Evolved optical performance

Nikon's CFI₆₀ optical system, highly evaluated for its unique concept of high NA combined with long working distance has further evolved to achieve the apex in long working distance, chromatic aberration correction, and light weight.

Easy Operation

Integration with digital camera

Detection of microscope information, including objective lens information, and motorized unit microscope operation are now possible using the digital control unit, for more efficient observation and image capture.

Observation Methods

Diverse observation methods

Combinations of a full range of accessories expand the observation methods available when using transmitted illumination, allowing adaptability to a greater diversity of samples.

All models enable brightfield, darkfield, differential interference, fluorescence, polarizing, and two-beam interferometry observation, while the LV100DA and LV100DA-U also allow transmission-type differential interference, darkfield, polarizing, and phase contrast observation.



LV-N Series

Model features



LV150N

NEW

LV150NL

(*Dedicated LED illumination models)



LV150NA

NEW

Dedicated reflected illumination models

Microscope type

Manual type

Motorized type
(Nosepiece)

Compatible observation methods

| | | Brightfield | Darkfield | DIC | Fluorescence | Polarizing | Phase-contrast | Two-beam Interferometry |
|-------------------|-----------|-------------|-----------|-----|--------------|------------|----------------|-------------------------|
| LV150/ LV150NA | Episcopic | ○ | ○ | ○ | ○ | ○ | — | ○ |
| LV150NL | | ○ | — | ○ | — | ○ | — | ○ |

* Use an objective lens appropriate to the observation method.

Compatible stages

- LV-S32 3x2 stage (Stroke: 75 x 50 mm with glass plate)
*Can be fitted with LV-S32SPL ESD plate
- LV-S6 6x6 stage (Stroke: 150 x 150 mm)
*Can be fitted with LV-S6WH wafer holder / LV-S6PL ESD plate
- LV-SRP P revolving stage
- P-GS2 G stage 2 (Used with stage adapter LV-SAD)

Integration with Digital Sight microscopic digital camera

DS-L3 (Stand alone control unit)

- Objective lens information detection
(when used with combination of Intelligent Nosepiece LV-NU5I and LV-INAD)

- Objective lens information detection and control



DS-U3 + NIS-Elements (PC control-based control unit + imaging software)

- Objective lens information detection
(when used with combination of Intelligent Nosepiece LV-NU5I and LV-INAD)

- Objective lens information detection and control



LV100ND

NEW



LV100DA-U

Combined reflected/transmitted illumination models

Manual type

Motorized type
(Nosepiece / light intensity / aperture stop / observation method selector)

| | | Brightfield | Darkfield | DIC | Fluorescence | Polarizing | Phase-contrast | Two-beam Interferometry |
|-----------------------|-----------|-------------|-----------|-----|--------------|------------|----------------|-------------------------|
| LV100ND/ LV100DA-U | Episcopic | ○ | ○ | ○ | ○ | ○ | — | ○ |
| | Diascopic | ○ | ○ | ○ | — | ○ | ○ | — |

* Use an objective lens appropriate to the observation method.

- LV-S32 3x2 stage (Stroke: 75 x 50 mm with glass plate)
*Can be fitted with LV-S32SGH slide glass holder
- LV-S64 6x4 stage (Stroke: 150 x 100 mm with glass plate)
- LV-SRP P revolving stage
- P-GS2 G stage 2 (Used with stage adapter LV-SAD)
- NIU-CSRR2 Ni-U right handle rotatable ceramic stage (Stroke: 78 x 54 mm)
- C-SR2S right handle stage (Stroke: 78 x 54 mm: Used with stage adapter LV-SAD)

DS-L3 (Stand alone control unit)

- Objective lens information detection
(when used with combination of Intelligent Nosepiece LV-NU5I and LV-INAD)

- Information detection of objective lens, light intensity, aperture stop, and observation method
(brightfield / darkfield / fluorescence)



DS-U3 + NIS-Elements (PC control-based control unit + imaging software)

- Objective lens information detection
(when used with combination of Intelligent Nosepiece LV-NU5I and LV-INAD)

- Information detection and control of objective lens, light intensity, aperture stop, and observation method
(brightfield / darkfield / fluorescence)



Evolved optical performance

Nikon's CFI60 optical system, highly evaluated for its unique concept of high NA combined with long working distance has further evolved to achieve the apex in long working distance, chromatic aberration correction, and light weight.

T Plan & TU Plan Fluor & TU Plan Apo Lenses

Standard Plan objective lenses

Standard objective lenses

TU Plan Fluor series

EPI/BD 5x/10x/20x/50x/100x

These universal type standard objective lenses enable brightfield, darkfield, simple polarizing, sensitive polarizing, differential interference, and epi-fluorescence observation in one lens. New semi-apochromatic lenses combine superior chromatic aberration performance with long working distance at all magnifications to adapt to any application.

Long WD

Semi-apo

Light weight

Fly's eye lens

* Depicted is the brightfield observation (EPI) objective lens.

| Model | Magnification | NA | Working Distance (mm) |
|---|---------------|------|-----------------------|
| TU Plan Fluor EPI (brightfield type) | 5x | 0.15 | 23.5 |
| | 10x | 0.30 | 17.5 |
| | 20x | 0.45 | 4.5 |
| | 50x | 0.80 | 1.0 |
| | 100x | 0.90 | 1.0 |
| TU Plan Fluor BD (brightfield/darkfield type) | 5x | 0.15 | 18.0 |
| | 10x | 0.30 | 15.0 |
| | * 20x | 0.45 | 4.5 |
| | * 50x | 0.80 | 1.0 |
| | * 100x | 0.90 | 1.0 |

* Uses fly's eye lenses.

Low-magnification objective lenses

T Plan EPI

EPI 1x/2.5x

These low-magnification objective lenses enable clear observation using a conventional analyzer/polarizer, as well as operability-oriented observation without need for an analyzer/polarizer.

Semi-apo

Wide field of view

| Model | Magnification | NA | Working Distance (mm) |
|-------------------------------|---------------|-------|-----------------------|
| T Plan EPI (brightfield type) | 1x | 0.03 | 3.8 |
| | 2.5x | 0.075 | 6.5 |

Apochromatic objective lenses

TU Plan Apo series

EPI/BD 50x/100x/150x

By using phase Fresnel lenses, these objective lenses achieve significantly longer operating distances while maintaining the superior chromatic aberration performance of apochromatic lenses. A 50x lens is new to the line-up.

Long WD

Apo

Light weight

* Depicted is the brightfield observation (EPI) objective lens.

| Model | Magnification | NA | Working Distance (mm) |
|---|---------------|-----|-----------------------|
| TU Plan Apo EPI (brightfield type) | 50x | 0.8 | 2.0 |
| | 100x | 0.9 | 2.0 |
| | 150x | 0.9 | 1.5 |
| TU Plan Apo BD (brightfield/darkfield type) | 50x | 0.8 | 2.0 |
| | 100x | 0.9 | 2.0 |
| | 150x | 0.9 | 1.5 |

Dark Field Illumination

Fly's eye lens

As low-magnification lenses normally have a wide actual field of view, it is difficult to achieve bright illumination without unevenness. Through the use of fly's eye lenses, the CFI60-2 optical system offers bright darkfield illumination throughout the field of view, with little unevenness.

Fly's eye lenses adjust the diffusion angle of light so light strikes the focal surface without unevenness

New darkfield illumination system

As NA and W.D. improve, objective lenses increase in outside diameter. However, as the width of incident light is fixed, light intensity decreases with conventional illumination systems. The new illumination system uses annular lenses or annular prisms to increase captured light and achieve bright darkfield illumination with no deterioration.

Annular lenses/prisms take in more light to increase brightness

TU Plan ELWD & T Plan SLWD Lenses

Long working distance / Super-long working distance objective lenses

Long working distance objective lenses

TU Plan ELWD Series

EPI/BD 20x/50x/100x

Through the use of phase Fresnel lenses, these objective lenses enable long working distances while offering higher-level chromatic aberration correction than conventional objective lenses. This further improves operability for samples with differences in level.

Long WD

Semi-apo

Light weight

* Depicted is the brightfield observation (EPI) objective lens.

| Model | Magnification | NA | Working Distance (mm) |
|--|---------------|-----|-----------------------|
| TU Plan EPI ELWD (brightfield type) | 20x | 0.4 | 19.0 |
| | 50x | 0.6 | 11.0 |
| | 100x | 0.8 | 4.5 |
| TU Plan BD ELWD (brightfield/darkfield type) | * 20x | 0.4 | 19.0 |
| | * 50x | 0.6 | 11.0 |
| | * 100x | 0.8 | 4.5 |

* Uses new darkfield illumination system.

Super-long working distance objective lenses

T Plan EPI SLWD

EPI 10x/20x/50x/100x

Improving on chromatic aberration while further advancing the concept of prioritizing working distance, the T Plan SLWD Series of super-long working distance semi-apochromatic objective lenses achieves best-in-class super-long working distance. The new addition of a SLWD 10x (WD: 37mm) lens to the line-up enables use with a greater diversity of samples.

Long WD

Semi-apo

Light weight

* Scheduled for sale from January 2013.

| Model | Magnification | NA | Working Distance (mm) |
|------------------------------------|---------------|-----|-----------------------|
| T Plan EPI SLWD (brightfield type) | 10x | 0.2 | 37.0 |
| | 20x | 0.3 | 30.0 |
| | 50x | 0.4 | 22.0 |
| | 100x | 0.6 | 10.0 |

Phase Fresnel

Color aberration correction

Conventional lenses rely upon the refraction of light to form an image. As the strength of refraction varies according to color (wavelength), the image is formed in the order of blue, green, and red, starting with light closest to the lens. In contrast, a phase Fresnel lens uses diffraction of light to form an image in the order of red, green, and blue, starting with light closest to the lens, thus yielding a property opposite that of refraction. Combining these two lenses cancels out the color aberration of each and enables an image with little color aberration.

Realization of Long Working Distance

Through the use of phase Fresnel lenses, correction of color aberration is possible even with short distances between lenses, enabling a longer working distance than possible with conventional lenses.

Other objective lenses

Objective lenses with glass thickness correction features

CFI L Plan EPI CR

20x/50x/100x

These objective lenses are equipped with corrective features that enable high-contrast observation of cells or patterns, unaffected by the glass substrate.

| Model | Magnification | NA | Working Distance (mm) |
|--------------------------------------|---------------|------|-----------------------|
| CFI L Plan EPI CR (brightfield type) | 20x CR | 0.45 | 10.90 - 10.00 |
| | 50x CR | 0.70 | 3.90 - 3.00 |
| | 100x CRA | 0.85 | 1.20 - 0.85 |
| | 100x CRB | 0.85 | 1.30 - 0.95 |

Objective lenses for interferometry / Objective lenses for two-beam interferometry

CF IC EPI Plan TI/DI

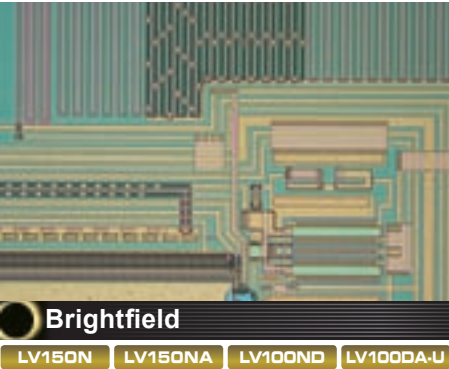
DI 10x/20x/50x/100x TI 2.5x/5x

These Michelson (TI) and Mirau (DI) two-beam interferometry lenses allow inspection and measurement of fine level differences without contact with the sample.

| Model | Magnification | NA | Working Distance (mm) |
|---|---------------|-------|-----------------------|
| CF IC EPI Plan TI (for interferometry) | 2.5xA | 0.075 | 10.30 |
| | 5xA | 0.130 | 9.30 |
| CF IC EPI Plan DI (for two-beam interferometry) | 10xA | 0.30 | 7.40 |
| | 20xA | 0.40 | 4.70 |
| | 50xA | 0.55 | 3.40 |
| | 100x | 0.70 | 2.00 |

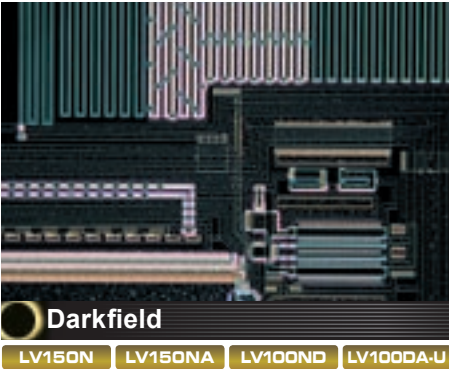
Observation Methods

Compatible with a wide range of observation methods: brightfield, darkfield, polarizing, differential interference, epi-fluorescence, and two-beam interferometry.



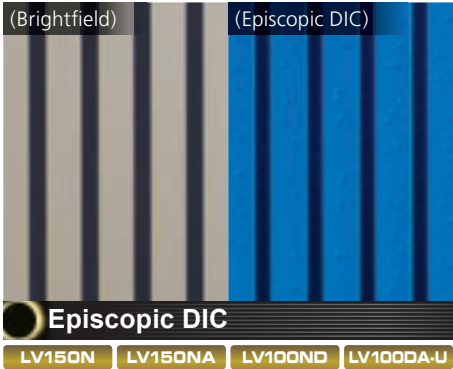
Semiconductors (IC wafers)

From its objective lenses to its illumination systems, the LV-N Series offers thorough measures against flare and provides bright, high-contrast images.



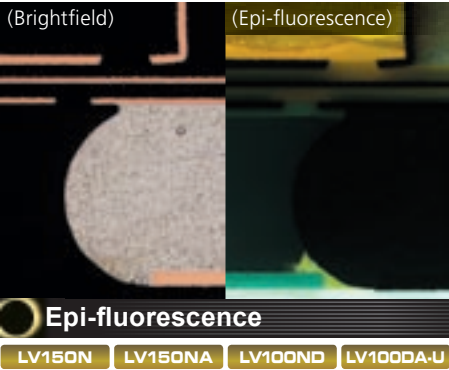
Semiconductors (IC wafers)

The use of Nikon's unique concepts in the objective lens darkfield illumination system enables bright darkfield observation and provides high-sensitivity detection of level differences and defects in samples.



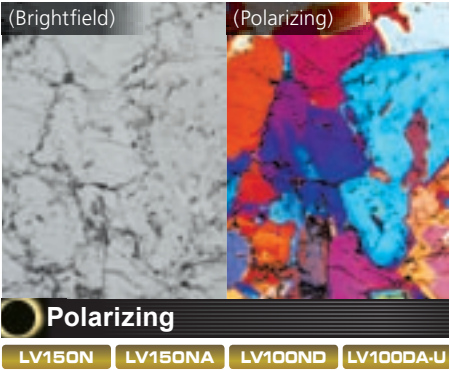
Substrate

Standard-type and high-contrast-type DIC sliders are available to match samples. The LV-N Series is effective for applications such as observation of minute level differences in devices and precision molds.



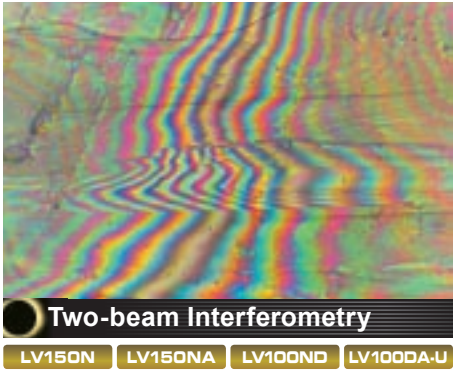
Substrate (solder)

The LV-N Series demonstrates superiority in the observation of samples with fluorescent properties, such as organic ELs or mounted substrates.



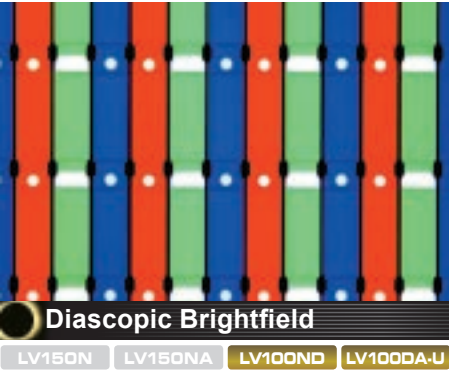
Minerals

The LV-N Series is effective in the observation of samples with birefringent properties, such as liquid crystals or plastics/glass containing distortion.



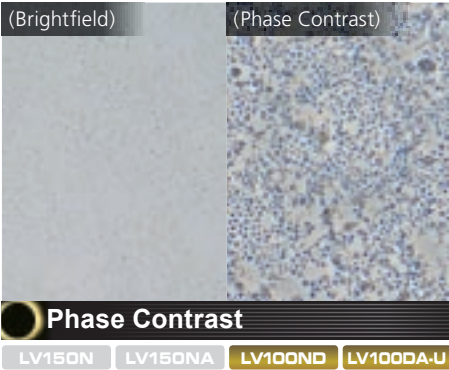
Mica

Michelson (TI) and Mirau (DI) reflection-type two-beam interferometry is possible with the LV-N Series. When used with micrometer eyepieces, minute level differences can be detected and measured without contact with the sample.



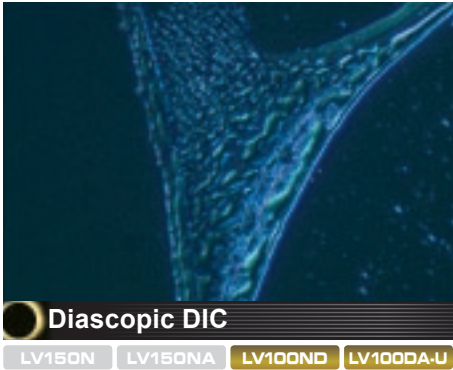
LCD (color filter)

The LV-N Series is effective in the observation of samples with transparency, such as optical components, FPDs, and slide glass samples. When used in conjunction with the C-SP Simple Polarizer and analyzers, transmitted simple polarized observation is possible.



Emulsion

Colorless, transparent samples can be made visible through bright/dark contrast and the use of diffraction and interference, two properties of light.



Nanoparticle (silver)






Colorless, transparent samples can be observed in three dimensions by using polarization to create interference between two beams of light.



Specifications

| | LV150N | LV150NA | LV150NL |
|-----------------------|--|---|--|
| Base unit | Maximum sample height: 38 mm (when used with LVNU5AI U5AI nosepiece and LV-S32 3x2 stage / LV-S64 6x4 stage) * 73 mm when used with one column riser 12V50W internal power source for dimmer, coarse and fine adjustment knobs Left: coarse and fine adjustment / Right: fine adjustment, 40 mm stroke Coarse adjustment: 14 mm/turn (with torque adjustment, refocusing mechanism) Fine adjustment: 0.1 mm/turn (1 μm/graduation) Stage mounting hole intervals: 70 x 94 (fixed by 4-M4 screw) | | Maximum sample height: 38 mm (when used with LV-S32 3x2 stage) * 73 mm when used with one column riser Internal LED illumination power source, coarse and fine adjustment knobs Left: coarse and fine adjustment / Right: fine adjustment, 40mm stroke Coarse adjustment: 14 mm/turn (with torque adjustment, refocusing mechanism) Fine adjustment: 0.1 mm/turn (1 μm/graduation) Stage mounting hole intervals: 70 x 94 (fixed by 4-M4 screw) |
| Nosepieces | C-N6 ESD Sextuple Nosepiece ESD LV-NU5 Universal Quintuple Nosepiece ESD LV-NBD5 BD Quintuple Nosepiece ESD LV-NU5I Intelligent Universal Quintuple Nosepiece ESD | LV-NU5A Motorized Universal Quintuple Nosepiece ESD LV-NU5AC Motorized Universal Quintuple Nosepiece ESD | C-N6 ESD Sextuple Nosepiece ESD LV-NU5 Universal Quintuple Nosepiece ESD |
| Episcopic Illuminator | LV-UEPI-N LV-LH50PC 12V50W Precentered Lamphouse Bright/darkfield switch and linked aperture stop (centerable), field diaphragm (centerable) Accepts ø 25 mm filter (NCB11, ND16, ND4), polarizer/analyzer, λ plate, excitation light balancer; equipped with noise terminator LV-UEPI2 LV-LH50PC 12V50W Precentered Lamphouse HG precentered fiber illuminator: C-HGFIE (with light adjustment) *option Bright/darkfield switch and linked aperture stop (centerable), field diaphragm (centerable), automated optical element switching feature matched to brightfield, darkfield, and epi-fluorescence switch Accepts ø 25 mm filter (NCB11, ND16, ND4), polarizer/analyzer, λ plate, excitation light balancer; equipped with noise terminator | | 1.1W white LED Accepts polarizer/analyzer |
| Eyepiece tubes | LV-TI3 trinocular eyepiece tube ESD (Erected image, FOV: 22/25) LV-TT2 TT2 tilting trinocular eyepiece tube (Erected image, FOV: 22/25) C-TB binocular tube (Inverted image, FOV: 22) P-TB Binocular Tube (Inverted image, FOV: 22) P-TT2 Trinocular Tube (Inverted image, FOV: 22) | | LV-TI3 trinocular eyepiece tube ESD (Erected image, FOV: 22/25) C-TB binocular tube (Inverted image, FOV: 22) P-TB Binocular Tube (Inverted image, FOV: 22) P-TT2 Trinocular Tube (Inverted image, FOV: 22) |
| Stages | LV-S32 3x2 stage (Stroke: 75 x 50 mm with glass plate) ESD compatible LV-S64 6x4 stage (Stroke: 150 x 100 mm with glass plate) ESD compatible LV-S6 6x6 stage (Stroke: 150 x 150 mm) ESD compatible | | LV-S32 3x2 stage (Stroke: 75 x 50 mm with glass plate) ESD compatible LV-S6 6x6 stage (Stroke: 150 x 150 mm) ESD compatible |
| Eyepieces | CFI eyepiece series | | |
| Objective lenses | Industrial Microscope CFI ₆₀ -2/CFI ₆₀ optical system Objective lens series: Combinations in accordance with the method | | |
| ESD performance | 1,000 to 10V, within 0.2 sec. (excluding certain accessories) | | |
| Power consumption | 1.2 A / 90 W | | 0.1A / 3W |
| Weight | Approx. 8.6 kg | Approx. 8.7 kg | Approx. 8.6 kg |

| | LV100ND | LV100DA-U |
|------------------------|--|--|
| Base unit | Maximum sample height: 38 mm (when used with LVNU5AI U5AI nosepiece and LV-S32 3x2 stage / LV-S64 6x4 stage) 12V50W internal power source for dimmer, coarse and fine adjustment knobs Left: coarse and fine adjustment / Right: fine adjustment, 40 mm stroke Coarse adjustment: 14 mm/turn (with torque adjustment, refocusing mechanism) Fine adjustment: 0.1 mm/turn (1 μm/graduation) | Maximum sample height: 33 mm (when used with LVNU5AI U5AI nosepiece and LV-S32 3x2 stage / LV-S64 6x4 stage) 12V50W internal power source for dimmer, coarse and fine adjustment knobs Left: coarse and fine adjustment / Right: fine adjustment, 40 mm stroke Coarse adjustment: 14 mm/turn (with torque adjustment, refocusing mechanism) Fine adjustment: 0.1 mm/turn (1 μm/graduation) |
| Nosepieces | C-N6 ESD Sextuple Nosepiece ESD, LV-NU5 Universal Quintuple Nosepiece ESD LV-NBD5 BD Quintuple Nosepiece ESD, LV-NU5I Intelligent Universal Quintuple Nosepiece ESD D-ND6 Sextuple DIC Nosepiece | LV-NU5AI Motorized Universal Quintuple Nosepiece (High-durability motorized 5-hole universal nosepiece) |
| Episcopic Illuminators | LV-UEPI-N LV-LH50PC 12V50W Precentered Lamphouse Bright/darkfield switch and linked aperture stop (centerable), field diaphragm (centerable), accepts ø 25 mm filter (NCB11, ND16, ND4), polarizer/analyzer; equipped with noise terminator LV-UEPI2 LV-LH50PC 12V50W Precentered Lamphouse HG precentered fiber illuminator: C-HGFIE (with light adjustment) *option Bright/darkfield switch and linked aperture stop (centerable), field diaphragm (centerable), automated optical element switching feature matched to brightfield, darkfield, and epi-fluorescence switch Accepts ø 25 mm filter (NCB11, ND16, ND4), polarizer/analyzer, λ plate, excitation light balancer; equipped with noise terminator | LV-UEPI2A LV-LH50PC 12V50W Precentered Lamphouse HG precentered fiber illuminator: C-HGFIE (with light adjustment: PC controlled) *option Motorized operation and control of illumination selector turret Motorized aperture stop linked to bright/darkfield selector (automatic optimization matched to objective lens), field diaphragm (centerable) Accepts ø 25 mm filter (NCB11, ND16, ND4), polarizer/analyzer, λ plate, excitation light balancer; equipped with noise terminator |
| Diascopic Illuminator | LV-LH50PC 12V50W Precentered Lamphouse (Fly Eye optical system) Internal aperture, field diaphragm, filter (ND8, NCB11); transmitted/reflected selector switch; 12V100W also available (option) | |
| Eyepiece tubes | LV-TI3 trinocular eyepiece tube ESD (Erected image, FOV: 22/25), LV-TT2 TT2 tilting trinocular eyepiece tube (Erected image, FOV: 22/25), P-TB Binocular Tube (Inverted image, FOV: 22), P-TT2 Trinocular Tube (Inverted image, FOV: 22) | |
| Stages | LV-S32 3x2 stage (Stroke: 75 x 50 mm with glass plate) / LV-S32SGH slide glass holder LV-S64 6x4 stage (Stroke: 150 x 100 mm with glass plate), LV-SRP P revolving stage / P-GS2 revolving stage: Used with stage adapter LV-SAD NIU-CSRR2 Ni-U right handle rotatable ceramic stage (Stroke: 78 x 54 mm), C-SR2S right handle stage (Stroke: 78 x 54 mm: Used with stage adapter LV-SAD) | |
| Condensers | LWD achromat condenser (brightfield), LV-CUD U condenser dry (phase contrast, diascopic DIC, darkfield), Achromat 2x-100x slide condenser (brightfield), DF dry condenser (darkfield), and others | |
| Eyepieces | CFI eyepiece series | |
| Objective lenses | Industrial Microscope CFI ₆₀ -2/CFI ₆₀ optical system Objective lens series: Combinations in accordance with the method | |
| ESD performance | 1,000 to 10V, within 0.2 sec. (excluding certain accessories) | |
| Power consumption | 1.2 A / 75 W | |
| Weight | Approx. 9.5 kg | Approx. 10 kg |

Lens Specifications

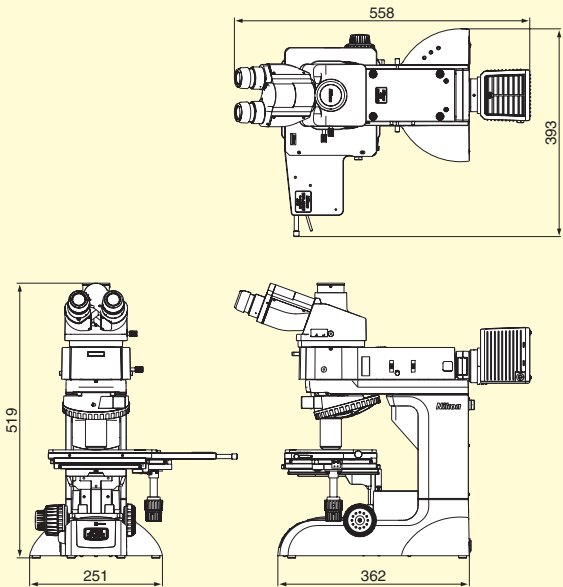
| | Type | Model | Magnification | Product Code No. | NA | Working Distance (mm) |
|---------|---|--|---------------|------------------|-------|-----------------------|
| CFI60-2 | Brightfield | T Plan EPI Plan (Semi-apochromat) | 1x | MUE12010 | 0.03 | 3.8 |
| | | | 2.5x | MUE12030 | 0.075 | 6.5 |
| | | TU Plan Fluor EPI Universal Plan Fluor (Semi-apochromat) | 5x | MUE12050 | 0.15 | 23.5 |
| | | | 10x | MUE12100 | 0.3 | 17.5 |
| | | | 20x | MUE12200 | 0.45 | 4.5 |
| | | | 50x | MUE12500 | 0.8 | 1.0 |
| | | | 100x | MUE12900 | 0.9 | 1.0 |
| | | TU Plan Apo EPI Universal Plan Apo (Apochromat)  | 50x | MUC11500 | 0.8 | 2.0 |
| | | | 100x | MUC11900 | 0.9 | 2.0 |
| | | | 150x | MUC11150 | 0.9 | 1.5 |
| | Polarizing | TU Plan Fluor EPI P Polarizing Universal Plan Fluor (Semi-apochromat) | 5x | MUE13050 | 0.15 | 23.5 |
| | | | 10x | MUE13100 | 0.3 | 17.5 |
| | | | 20x | MUE13200 | 0.45 | 4.5 |
| | | | 50x | MUE13500 | 0.8 | 1.0 |
| | | | 100x | MUE13900 | 0.9 | 1.0 |
| | Brightfield Long Working Distance | TU Plan EPI ELWD Long Working Distance Universal Plan (Semi-apochromat)  | 20x | MUE21200 | 0.4 | 19.0 |
| | | | 50x | MUE21500 | 0.6 | 11.0 |
| | | | 100x | MUE21900 | 0.8 | 4.5 |
| | Brightfield Super-long Working Distance | T Plan EPI SLWD Super-long Working Distance Plan (Semi-apochromat)  | 10x | MUE31100 | 0.2 | 37.0 |
| | | | 20x | MUE31200 | 0.3 | 30.0 |
| | | | 50x | MUE31500 | 0.4 | 22.0 |
| | | | 100x | MUE31900 | 0.6 | 10.0 |
| | Brightfield/Darkfield | TU Plan Fluor BD Universal Plan Fluor (Semi-apochromat) | 5x | MUE42050 | 0.15 | 18.0 |
| | | | 10x | MUE42100 | 0.3 | 15.0 |
| | | | 20x | MUE42200 | 0.45 | 4.5 |
| | | | 50x | MUE42500 | 0.8 | 1.0 |
| | | | 100x | MUE42900 | 0.9 | 1.0 |
| | | TU Plan Apo BD Universal Plan Apo (Apochromat)  | 50x | MUC41500 | 0.8 | 2.0 |
| | | | 100x | MUC41900 | 0.9 | 2.0 |
| | | | 150x | MUC41150 | 0.9 | 1.5 |
| | Brightfield/Darkfield Long Working Distance | TU Plan BD ELWD Long Working Distance Universal Plan (Semi-apochromat)  | 20x | MUE61200 | 0.4 | 19.0 |
| | | | 50x | MUE61500 | 0.6 | 11.0 |
| | | | 100x | MUE61900 | 0.8 | 4.5 |

●  : Phase Fresnel lens (diffraction optical element) type ●  : A circular polarizing plate and depolarizer are built into T Plan EPI 1x/2.5x. (Circular polarizing plate can be attached/detached.)

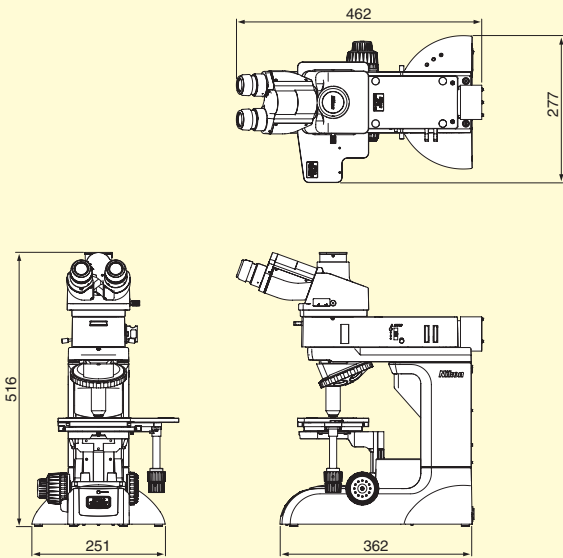
| | Type | Model | Magnification | Product Code No. | NA | Working Distance (mm) |
|-------|---|--|---------------|------------------|-------|-----------------------|
| CFI60 | Brightfield With Correction Mechanism | L Plan EPI CR For Inspecting LCDs Plan | 20x | MUE35200 | 0.45 | 10.9 - 10.0 |
| | | | 50x | MUE35500 | 0.7 | 3.9 - 3.0 |
| | | | 100x | MUE35900 | 0.85 | 1.2 - 0.85 |
| | | | 100x | MUE35910 | 0.85 | 1.3 - 0.95 |
| | Brightfield | L Plan EPI Plan (Achromat) | 40x | MUE00400 | 0.65 | 1.0 |
| | Brightfield Super-long Working Distance | LU Plan EPI SLWD Super-long Working Distance Plan (Achromat) | 20x | MUE30201 | 0.35 | 24.0 |
| | | | 50x | MUE30501 | 0.45 | 17.0 |
| | | | 100x | MUE30901 | 0.7 | 6.5 |
| | Brightfield | LU Plan Apo EPI Universal Plan Apo (Apochromat) | 100x | MUC00090 | 0.95 | 0.4 |
| | | | 150x | MUC10151 | 0.95 | 0.3 |
| | Brightfield/Darkfield | LU Plan Apo BD Universal Plan Apo (Apochromat) | 100x | MUC40900 | 0.9 | 0.51 |
| | | | 150x | MUC50151 | 0.9 | 0.42 |
| CF&IC | Interferometry | CF IC EPI Plan TI For Interferometry Plan | 2.5x | MUL42031 | 0.075 | 10.3 |
| | | | 5x | MUL42051 | 0.13 | 9.3 |
| | | CF IC EPI Plan DI For Two-beam Interferometry Plan | 10x | MUL40101 | 0.3 | 7.4 |
| | | | 20x | MUL40201 | 0.4 | 4.7 |
| | | | 50x | MUL40501 | 0.55 | 3.4 |
| | | | 100x | MUL40900 | 0.7 | 2.0 |
| | Brightfield | CF IC EPI Plan Apo Plan Apochromat | 50x | MUT10051 | 0.95 | 0.4 |
| | | | 100x | MUT10101 | 0.95 | 0.3 |
| | | | 150x | MUT10153 | 0.95 | 0.2 |

Dimensions

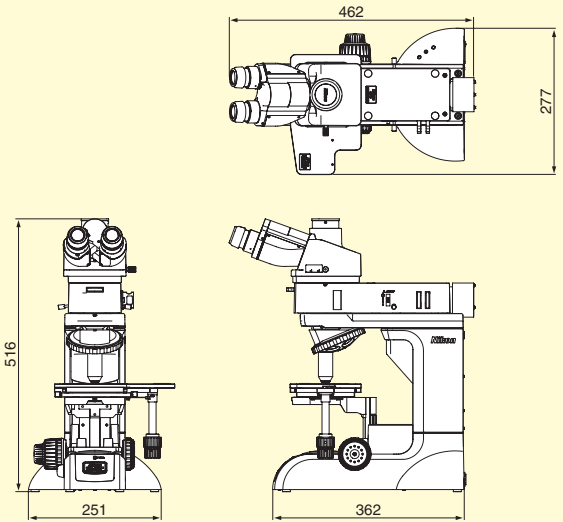
LV150N / LV150NA



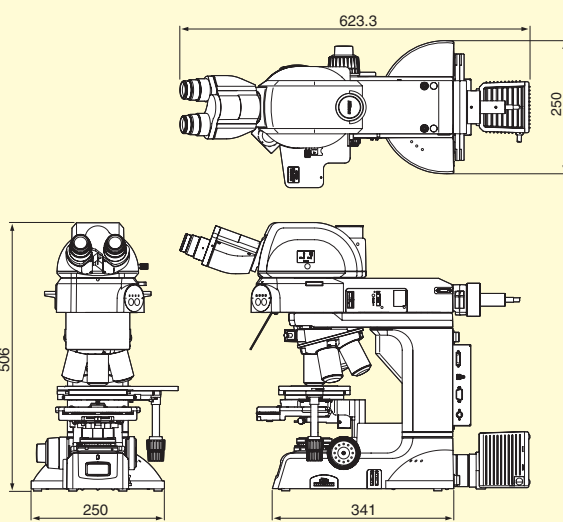
LV150NL



LV100ND

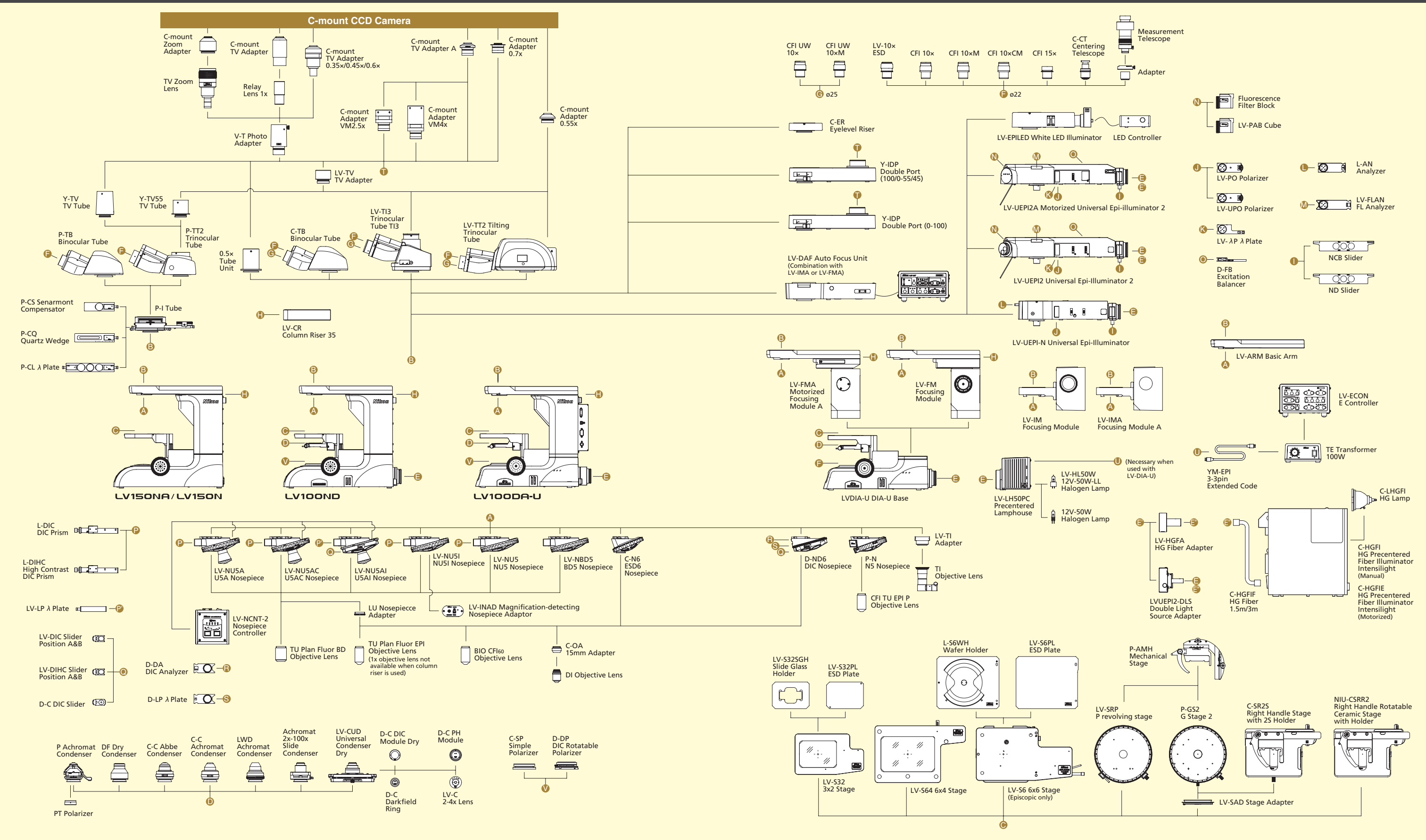


LV100DA-U



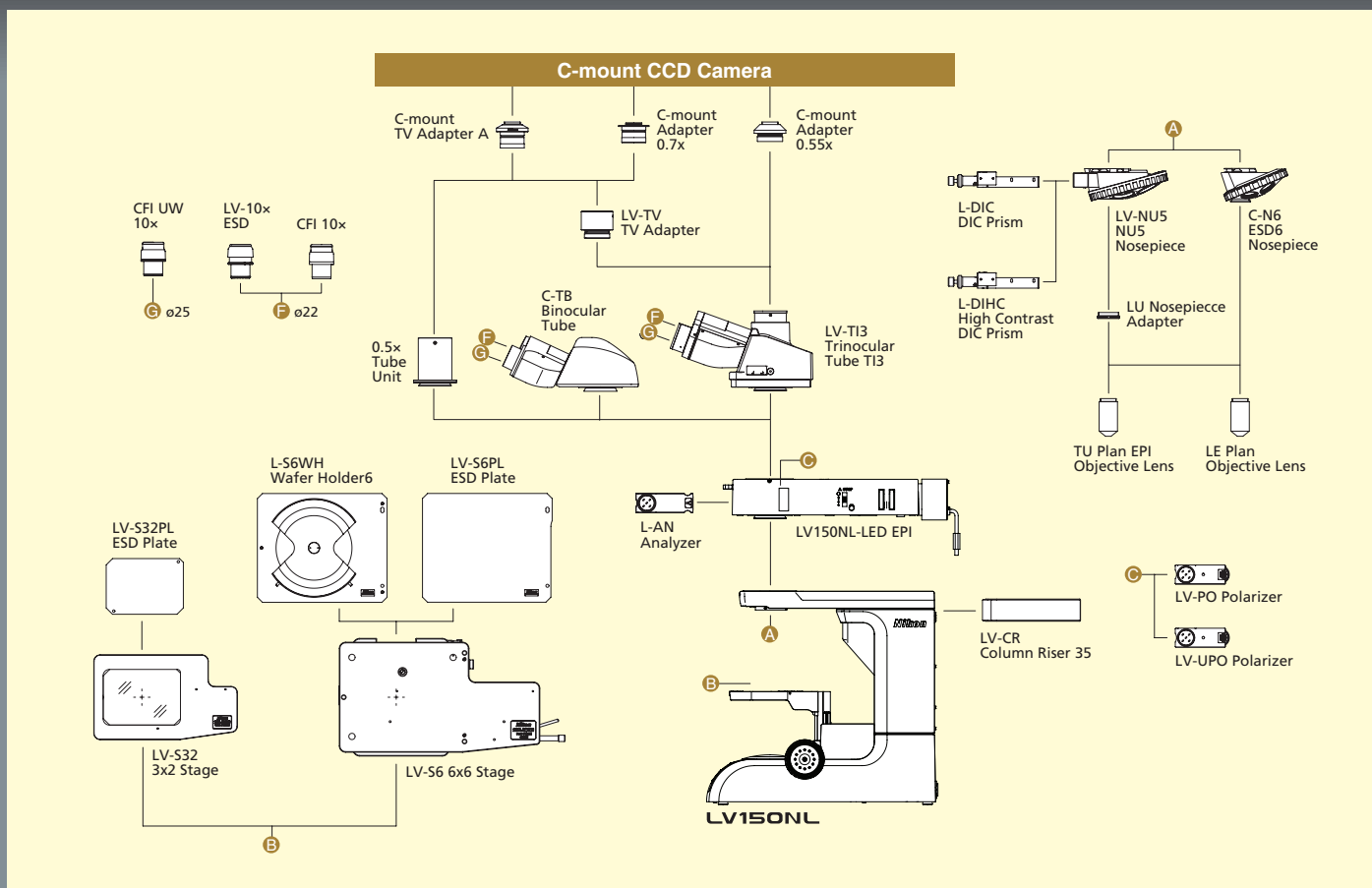
System Diagram

for LV150N/LV150ND/LV100NDA/LV100DA-U



System Diagram

for LV150NL



Specifications and equipment are subject to change without any notice or obligation on the part of the manufacturer. September 2012 ©2012 NIKON CORPORATION

N.B. Export of the products* in this catalog is controlled under the Japanese Foreign Exchange and Foreign Trade Law. Appropriate export procedures shall be required in case of export from Japan.

*Products: Hardware and its technical information (including software)



WARNING

TO ENSURE CORRECT USAGE, READ THE CORRESPONDING MANUALS CAREFULLY BEFORE USING THE EQUIPMENT.



NIKON CORPORATION

Shin-Yurakucho Bldg., 12-1, Yurakucho 1-chome
Chiyoda-ku, Tokyo 100-8331 Japan
phone: +81-3-3216-2384 fax: +81-3-3216-2388
<http://www.nikon.com/instruments/>



ISO 9001 Certified
for NIKON CORPORATION
Instruments Company



ISO 14001 Certified
for NIKON CORPORATION
Yokohama Plant

NIKON METROLOGY, INC.

12701 Grand River Avenue, Brighton, MI 48116 U.S.A.
phone: +1-810-220-4360 fax: +1-810-220-4300
E-mail: sales_us@nikonmetrology.com
<http://us.nikonmetrology.com/>
<http://www.nikoninstruments.com/>

NIKON METROLOGY EUROPE NV

Geldenaaksebaan 329, 3001 Leuven, Belgium
phone: +32-16-74-01-00 fax: +32-16-74-01-03
Email: sales_europe@nikonmetrology.com
<http://www.nikonmetrology.com/>

NIKON INSTRUMENTS (SHANGHAI) CO., LTD.

CHINA phone: +86-21-6841-2050 fax: +86-21-6841-2060
(Beijing branch) phone: +86-10-5831-2028 fax: +86-10-5831-2026
(Guangzhou branch) phone: +86-20-3882-0550 fax: +86-20-3882-0580

NIKON SINGAPORE PTE LTD.

SINGAPORE phone: +65-6559-3618 fax: +65-6559-3668

NIKON MALAYSIA SDN. BHD.

MALAYSIA phone: +60-3-7809-3688 fax: +60-3-7809-3633

NIKON INSTRUMENTS KOREA CO., LTD.

KOREA phone: +82-2-2186-8400 fax: +82-2-555-4415

NIKON INDIA PRIVATE LIMITED

INDIA phone: +91-124-4688500 fax: +91-124-4688527

NIKON CANADA INC.

CANADA phone: +1-905-602-9676 fax: +1-905-602-9953

NIKON INSTRUMENTS S.p.A.

ITALY phone: +39-055-300-96-01 fax: +39-055-30-09-93

NIKON METROLOGY UK LTD.

UNITED KINGDOM phone: +44-1332-811-349 fax: +44-1332-639-881
E-mail: sales_uk@nikonmetrology.com

NIKON METROLOGY SARL

FRANCE phone: +33-1-60-86-09-76 fax: +33-1-60-86-57-35
E-mail: sales_france@nikonmetrology.com

NIKON METROLOGY GMBH

GERMANY phone: +49-6023-91733-0 fax: +49-6023-91733-229
E-mail: sales_germany@nikonmetrology.com